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(71)Applicant : SUMITOMO CHEM CO LTD

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(72)Inventor : BABA KOJI
HOZUMI SHIGEO
HAGA SHIGEO

(54) PHOTODETSETTING RESIN COMPOSITION

(57)Abstract:

PURPOSE: To obtain a photodeTsetting resin composition containing urethane (meth) acrylate, N-vinylpyrrolidone, tertiary amines and a photopolymerization initiator, having low viscosity, high curing property and reliability, excellent in storage stability and suitable for optical fiber coating materials.

CONSTITUTION: This composition is obtained by blending (A) 40-80wt.% of an urethane (meth) acrylate (preferably having 400-40000 number-average molecular weight) with (B) 5-30wt.% of N-vinylpyrrolidone and (C) 0.01-1wt.% of tertiary amines [e.g. 1,8-diazabicyclo[5,4,0]undecene-7] and (D) 0.5-7wt.% of an photopolymerization initiator (e.g. benzophenone). Furthermore, when a reactive diluent other than the component B is further included into the composition, e.g. an ethylenic unsaturated group-containing monofunctional compound such as butanediol mono (meth)acrylate can be used as the diluent.

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